



JETFIRST series

RTA-RTO-RTN
Bench top RTP processor

Reliable, cost efficient design for universities and research labs
Wafer size range from 100 to 300mm (4"-12")

The Jipelec JetFirst has been developed to meet the requirements of universities and research laboratories.

The temperature measurement control system provides accurate and repeatable thermal control across the temperature range.

The lamp array, upper flange and quartz window are mounted in a rotating top lid, giving full access to the chamber for easy loading and unloading of the wafer.

Silicon carbide coated graphite susceptors are available for processing of small samples and III-V, II-VI compounds.



A spare chamber can be provided upon request to avoid cross contamination if several processes have to be performed in the same equipment.

A square chamber concept has been especially designed for the photovoltaic applications.

Main features

- Bench top design up to 200 mm
- Evolutive and upgradable system
- Wafer sizes up to 300 mm
- Cold wall chamber technology
- Pyrometer and thermocouple controllers
- PID temperature control
- Atmospheric and high vacuum process capability
- Up to 3 gas lines with MFCs
- Process management software

Options

- Pumping and/or turbo pumping unit
- Quick fit 2-chamber design - spare chamber
- Photovoltaic chamber - square design
- Up to 6 gas lines

Applications

- RTA : Rapid Thermal Annealing
- RTO : Rapid Thermal Oxidation
- RTN : Rapid Thermal Nitridation
- RTD : Rapid Thermal Diffusion from spin-on dopants
- Crystallization
- Contact alloying
- Densification
- Firing

Features

Temperature range:	ambient to 1400°C
Ramp rate:	1°C/s to 400°C/s
Pyrometer control:	150°C to 1400°C
JetFirst dimensions (L/W/H):	850x750x675 mm
JetFirst 300 dimensions (L/W/H):	1000x900x1500 mm